

**Listing of Claims:**

1. (currently amended) An apparatus comprising:  
a material source means for supplying a material to be deposited;  
an atomization means for producing a plurality of discrete particles from said material source means;  
a force application means comprising a carrier gas for propelling said plurality of discrete particles generally toward a substrate; and  
a collimation means comprising a coflowing sheath gas which surrounds said carrier gas for controlling the direction of flight of said plurality of discrete particles.

2. (previously presented) The apparatus of claim 1 additionally comprising means for sorting said plurality of discrete particles by size.

3-9. (canceled)

10. (currently amended) The apparatus of claim [[9]] 1 wherein said coflowing sheath gas forms a boundary layer that prevents said plurality of discrete particles from depositing onto walls of an orifice nozzle.

11. (currently amended) A method of direct writing of a material, the method comprising the steps of:

supplying the material to be deposited;  
atomizing the material to produce a plurality of discrete particles;  
applying a force by employing a carrier gas to propel the plurality of discrete particles generally toward a substrate;  
collimating the plurality of discrete particles by surrounding the carrier gas with a coflowing sheath gas to control the direction of flight of the plurality of discrete particles; and  
depositing the plurality of discrete particles on the substrate.

12. (previously presented) The method of claim 11 additionally comprising the step of sorting the plurality of discrete particles by size.

13. (previously presented) The method of claim 12 wherein the sorting step comprises employing one or more virtual impactors.

14-19. (canceled)

20. (currently amended) The method of claim 19 11 further comprising the step of the coflowing sheath gas forming a boundary layer, thereby preventing the plurality of discrete particles from depositing onto walls of an orifice nozzle.

21. (currently amended) The apparatus of claim 1 further comprising a virtual ~~compactor~~ impactor.

22. (currently amended) The apparatus of claim 21 wherein said virtual ~~compactor~~  
impactor is placed after said atomization means.

23. (previously presented) The apparatus of claim 22 wherein said virtual impactor extracts  
excess carrier gas without substantially reducing the number of said discrete particles.

24. (previously presented) The apparatus of claim 22 wherein said virtual impactor sorts  
said plurality of discrete particles by size.

25. (previously presented) The apparatus of claim 22 further comprising two or more virtual  
impactors placed in series.

26. (previously presented) The apparatus of claim 1 further comprising a laser for  
processing said discrete particles.

27. (previously presented) The method of claim 11 further comprising the step of extracting  
excess carrier gas without substantially reducing the number of said discrete particles.

28. (currently amended) The method of claim 28 27 wherein the extracting step  
comprises employing a virtual impactor.

29. (previously presented) The method of claim 11 further comprising the step of placing  
two or more virtual impactors in series.

30. (previously presented) The method of claim 11 further comprising the step of processing the discrete particles with a laser.